



Contents lists available at ScienceDirect

## Journal of the Taiwan Institute of Chemical Engineers

journal homepage: [www.elsevier.com/locate/jtice](http://www.elsevier.com/locate/jtice)

# Crystallite growth and optical properties of cadmium oxide thin films annealed at various temperatures for various durations

Bo Huang<sup>a,1</sup>, Hsueh-Liang Chu<sup>b,1</sup>, Moo-Chin Wang<sup>c,d,\*</sup>, Weng-Sing Hwang<sup>b,e</sup>, Chao Liu<sup>a,\*\*</sup>,  
Xiujuan Zhao<sup>a,\*\*</sup>

<sup>a</sup> State Key Laboratory of Silicate Materials for Architectures, Wuhan University of Technology, Wuhan 430070, PR China

<sup>b</sup> Department of Materials Science and Engineering, National Cheng Kung University, 1 Ta-Hsueh Road, Tainan 70101, Taiwan

<sup>c</sup> Department of Fragrance and Cosmetic Science, Kaohsiung Medical University, 100 Shih-Chuan 1st Road, Kaohsiung 80708, Taiwan

<sup>d</sup> Department of Medical Research, Kaohsiung Medical University Hospital, 100 Tzyou 1st Road, Kaohsiung 80708, Taiwan

<sup>e</sup> Institute of Nanotechnology and Microsystems Engineering, National Cheng Kung University, 1 Ta-Hsueh Road, Tainan 70101, Taiwan

## ARTICLE INFO

## Article history:

Received 10 March 2017

Revised 2 June 2017

Accepted 6 July 2017

Available online xxx

## Keywords:

CdO thin films

Crystallite growth

Optical properties

## ABSTRACT

The crystallite growth and optical properties of cadmium oxide (CdO) thin films annealed at various temperatures and for various durations have been investigated using grazing incident X-ray diffraction (GID), high-resolution transmittance electron microscopy (HR-TEM), selected area electron diffraction, and ultraviolet-visible spectrometry. All the thin films were annealed between 573 and 773 K for 10 to 60 min, respectively. GID results showed that all thin films contain only a single phase of CdO with (111) preferential orientation. The crystallite size of CdO increases with increases in annealing temperature and duration. It was found that the CdO crystallites followed a normal growth with an average activation energy of  $13.04 \pm 1.34$  kJ/mol when annealed at 573–773 K for 10–60 min. The transmission spectra showed that the band gap energies of CdO thin films decreased from 2.474 to 2.050 eV as the annealing temperature increased, while the thin films maintained highly transparent in the visible spectral range.

© 2017 Taiwan Institute of Chemical Engineers. Published by Elsevier B.V. All rights reserved.

## 1. Introduction

It has been reported that cadmium oxide (CdO) has a rock salt structure with a direct band gap of about 2.2 eV and a narrow indirect bandgap of about 0.5 eV exhibiting *n*-type conduction [1,2]. In 1907, CdO thin films as a transparent conductor were first reported by Badeker [3]. From the point of view of applications, CdO films have been used in various fields such as solar cells [2,4], gas sensors [5,6], photodetectors [3,5], nonlinear optics [7], and so on.

The conductivity of CdO thin films can be controlled by the production of Cd interstitials and/or oxygen vacancies and they can be fabricated by various processes with different metallic ions [8–17]. However, when CdO thin films with various doping elements were fabricated by liquid phase deposition techniques, only *n*-type CdO thin films were obtained due to the native oxygen vacancy in the CdO thin films [18].

In addition, many researchers also studied the carrier mechanism and properties of undoped CdO thin films fabricated using different processes [19–24]. Use of atmospheric pressure chemical vapor deposition to synthesize undoped CdO thin films has been reported by Terasako et al. [19]. They found that the *n*-type carrier concentrations were  $2.4 \times 10^{19}$  and  $2.0 \times 10^{20}$  cm<sup>-3</sup> for CdO thin films grown on *c*- and *r*-plane sapphire substrates, respectively. The fundamental direct band gap decreased from 2.31 to 2.18 eV when the temperature rose from 0 to 300 K for CdO thin films deposited on sapphire substrates synthesized by the metal organic vapor phase epitaxy process [20]. Use of the successive ionic layer absorption and reaction (SILAR) method for preparation of CdO thin films has been reported by Salunkhe et al. [21]. They revealed that after annealing of CdO thin films, pure cubic CdO was obtained because the H<sub>2</sub>O vapors from as-deposited Cd(O<sub>2</sub>)<sub>0.88</sub>(OH)<sub>0.24</sub> were removed, creating CdO [21]. Bhosale et al. [22] also used the spray pyrolysis technique to synthesize undoped CdO thin films and reported that the films were polycrystalline with cubic structure, having better orientation along the (111) reflection of CdO after deposition at a substrate temperature and cadmium acetate concentration of 673 K and 0.1 M, respectively. A single-phase layer of CdO was obtained when CdO thin films were prepared by chemical spray pyrolysis at substrate temperatures higher than 448 K.

\* Corresponding author at: Department of Fragrance and Cosmetic Science, Kaohsiung Medical University, 100 Shih-Chuan 1st Road, Kaohsiung 80708, Taiwan.

\*\* Corresponding authors.

E-mail addresses: [mcwang@kmu.edu.tw](mailto:mcwang@kmu.edu.tw) (M.-C. Wang), [hite@whut.edu.cn](mailto:hite@whut.edu.cn) (C. Liu), [opluse@whut.edu.cn](mailto:opluse@whut.edu.cn) (X. Zhao).

<sup>1</sup> Both the authors contributed equally to this work.

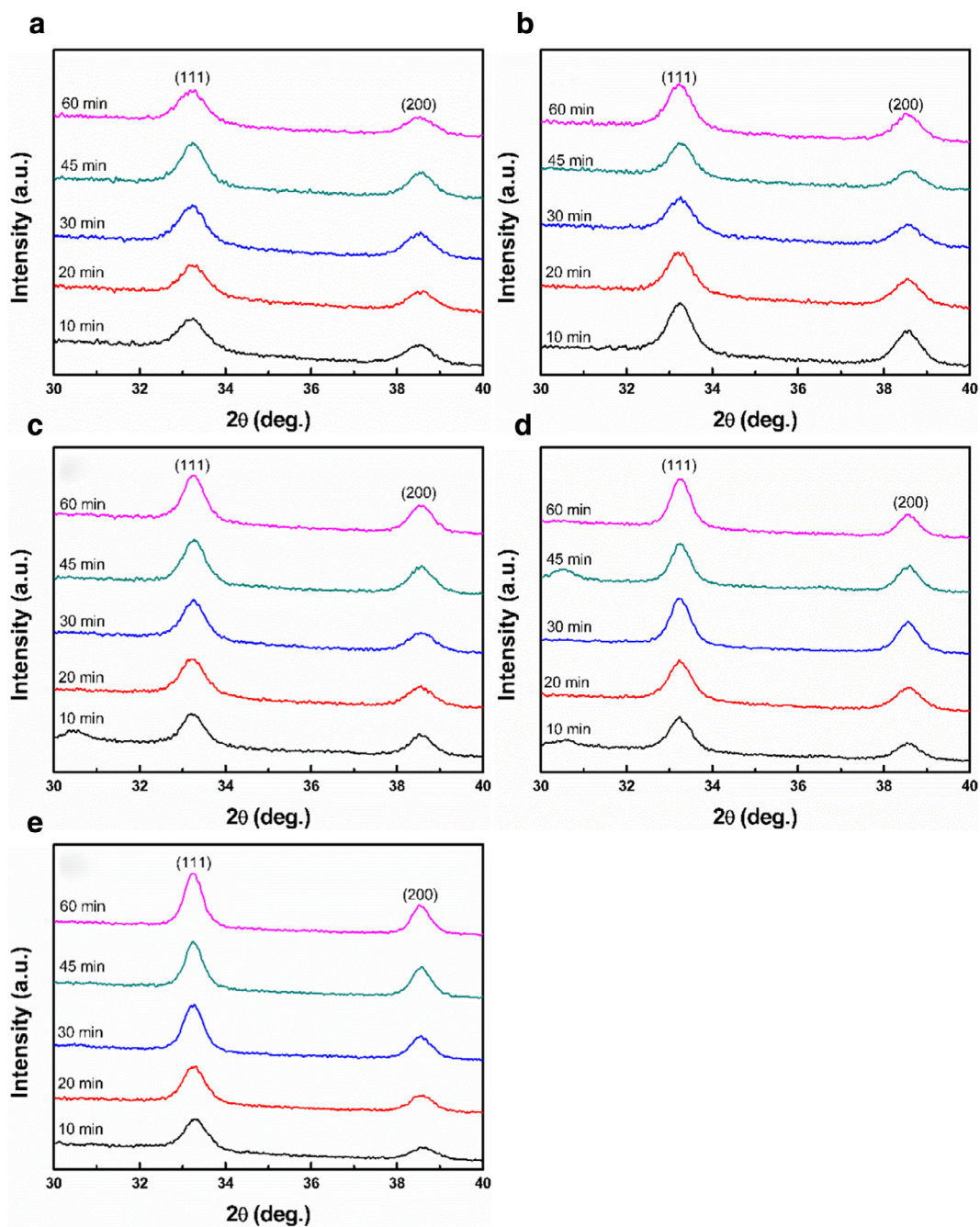


Fig. 1. XRD patterns of CdO thin films after annealing at various temperatures for different durations: (a) 573 K, (b) 623 K, (c) 673 K, (d) 723 K, and (e) 773 K.

The optical band gap energy of CdO thin films increased from 2.32 to 2.54 eV when the substrate temperature rose from 373 to 523 K [23]. Undoped CdO thin films were successfully deposited on glass substrates by the direct current magnetron sputtering process at 623 K in a partial pressure range of oxygen from  $1 \times 10^{-4}$  to  $5 \times 10^{-3}$  mbar. The electrical resistivity and visible transmittance of the obtained thin films were  $8.2 \times 10^{-4} \Omega \text{ m}$  and 85%, respectively, when the oxygen partial pressure was  $1 \times 10^{-3}$  mbar.

Moreover, undoped CdO thin films synthesized by the sol-gel process and their properties have also been studied by various researchers [25–28]. Using the sol-gel process, undoped CdO thin films were synthesized, and the effect of annealing on the surface morphology and optoelectronic properties were investigated by Ziabari and Ghodsi [25]. After annealing, these films possessed a cubic structure of polycrystalline CdO and the crystallinity

increased with rises in the annealing temperature. The band gap energy of these CdO thin films showed a blue-shift effect when they were annealed at temperatures between 523 and 623 K [25]. The effect of annealing temperature on the physical properties of undoped CdO thin films synthesized by a sol-gel spin coating process was also reported by Askoy et al. [26]. They revealed that the thin films contained polycrystalline CdO with (111) preferential orientation after annealing of the as-deposited thin films at 673, 773, and 873 K for 1 h, respectively. The optical band gap energies decreased from 2.47 to 2.22 eV with increases in the annealing temperature from 673 to 873 K [26]. Ghosh et al. [27] pointed out that the direct band gap energy lay in the range of 2.86 to 3.69 eV when CdO thin films were deposited on glass and Si substrates using the sol-gel dip coating process. These thin films have nearly 75% transparency in the wavelength range of 500 to 800 nm. In addition,

Download English Version:

<https://daneshyari.com/en/article/7105219>

Download Persian Version:

<https://daneshyari.com/article/7105219>

[Daneshyari.com](https://daneshyari.com)